DATA SHEET

SOLAR InDop

Inline doper with soft rollers

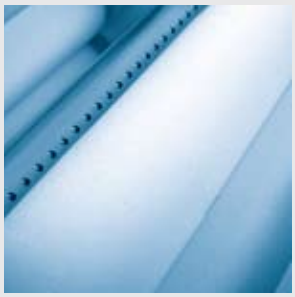
The InDop system applies a thin and homogeneous layer of phosphoric acid on the wafers before the inline diffusion process. The system offers optimal line integration with the RENA process equipment and automation thus simplifying the set-up of your front end. Using soft rollers to apply the phosphoric acid, it combines a robust process and low cost of ownership with an extremely gentle wafer transport system for highest mechanical and process yields.

Areas of application

- Roll-on application of phosphoric acid for inline phosphorus diffusion
- Designed for multi- and monocrystalline wafers
- Automation systems available for loading and transfer to the inline furnace - with flip and buffer options

Features and benefits

- Ideal line integration with RENA InTex systems
- Doping process adapted to the texture
- Double side coating for optimised P-gettering on both sides
- Low cost of ownership by using phosphoric acid as precursor
- Formation of a thin PSG layer, easy to remove
- Excellent process homogeneity
- Stable process control
- Online monitoring of the deposited phosphoric acid layer
- Best emitter profiles in combination with InOxSide EB



Roll-on system

Roll-on system

Front view InDop

Technical Data InDop

	InDop ST	InDop HT
	• 5 lanes for 156 mm wafers	• 5 lanes for 156 mm wafers
Process	Deposition of phosphoric acid for inline phosphorus diffusion	
Dimensions	3000 x 2150 x 2350 mm (length x width x height)	3000 x 2150 x 2350 mm (length x width x height)
Throughput	• 1875 wafers/h gross • wafer size 156 mm	• 3000 wafers/h gross • wafer size 156 mm
Wafer thickness	> 150 µm	> 150 µm

RENA August 2010

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